

Pr.

Group Art Unit: 2823

In re the Application of:

Akito KURAMATA et al.

Serial No.: 09/313,764

Filed: May 18, 1999 Examiner: W. Coleman

For: OPTICAL SEMICONDUCTOR DEVICE HAVING AN EPITAXIAL LAYER OF

III-V COMPOUND SEMICONDUCTOR MATERIAL CONTAINING N AS A

GROUP V ELEMENT

PRELIMINARY AMENDMENT

Commissioner for Patents Washington, D.C. 20231

April 30, 2002

Sir:

Prior to calculation of the filing fee and examination of this application, please amend the above-identified application as follows: 05/01/2002 JADD01 00000028 09313764

02 FC:103

72.00 OP

03 FC:102

420.00 OP

IN THE CLAIMS:

Please amend the claims 1 and 21 as follows:

- 1. (Amended) An optical semiconductor device, comprising:
- a substrate of SiC having a first conductivity type;
- a buffer layer of AlGaN formed on said substrate epitaxially, said buffer layer having said first conductivity type and a composition represented by a compositional parameter x as $Al_xGa_{1-x}N$;
- a first cladding layer having said first conductivity type, said first cladding layer being formed on said buffer layer epitaxially;

an active layer formed epitaxially on said first cladding layer;

